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1752
Atty Dkt No. ARC920010125US1

R&A No. 5075-0034

PATENT



Date

Signature

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re Application of:

Hiroshi ITO

Serial No.: 10/091,373

Group Art Unit: 1752

Filing Date: March 4, 2002

Examiner: Unassigned

Title: COPOLYMER FOR USE IN CHEMICAL AMPLIFICATION RESISTS

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
Washington, DC 20231

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OCT 29 2002

TC 1700

Sir:

This is a Supplemental Information Disclosure Statement submitted for the Examiner's consideration. Applicants respectfully request that the Examiner review and make of record the references identified below.

A PTO-1449 form listing the references accompanies this paper. Applicants would appreciate the Examiner's initialing and returning the form to indicate that the references have been reviewed and made of record. The references are as follows:

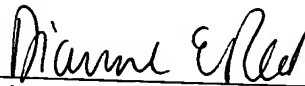
U.S. PATENT DOCUMENTS		
Document No.	Issue Date or Publication Date	Name of Patentee or Applicant
2002/0102490	8/1/02	Ito et al.
Serial No. 09/771,149	Filed 1/26/01	Ito et al.
Serial No. 09/771,261	Filed 1/26/01	Brock et al.
Serial No. 09/794,466	2/26/01	Allen et al.

NONPATENT DOCUMENTS	
Abe et al. (1995), "Study of ArF Resist Material in Terms of Transparency and Dry Etch Resistance," <i>Journal of Photopolymer Science and Technology</i> 8(4):637-642.	
Allen et al. (1995), "Resolution and Etch Resistance of a Family of 193 nm Positive Resists," <i>Journal of Photopolymer Science and Technology</i> 8(4):623-636.	
Ender et al. (1999), "Microstructuring with 157 nm Laser Light," <i>Proceedings of SPIE-The International Society for Optical Engineering</i> 3618:413-417.	
Onishi et al. (1991), "Acid Catalyzed Resist for KrF Excimer Laser Lithography," <i>Journal of Photopolymer Science and Technology</i> 4(3):337-340.	

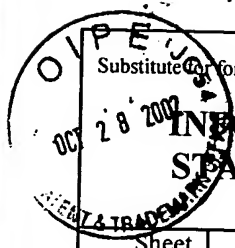
This Supplemental Information Disclosure Statement is not intended as a representation that a search has been made, that additional information material to the examination of this application does not exist, or that any of the above references constitutes prior art to the present application within the meaning of 35 USC § 102.

As applicants have not yet received a first Action on the merits, no fee is required for filing this Supplemental Information Disclosure Statement. If, however, the PTO finds that for some reason a fee is found to be necessary, our Deposit Account No. 18-0580 may be charged therefor. **A duplicate copy of this paper is enclosed.**

Respectfully submitted,

By: 
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Substitute Form 1449A/PTO

**INFORMATION DISCLOSURE
STATEMENT BY APPLICANT**

(use as many sheets as necessary)

Sheet

1

of

1

Complete if Known

Application Number	10/091,373
Filing Date	March 4, 2002
First Named Inventor	Hiroshi ITO
Art Unit	1752
Examiner Name	Unassigned
Attorney Docket Number	ARC920010125US1

U.S. PATENT DOCUMENTS

Examiner Initials*	Cite No.	Document No.	Issue Date or Publication Date	Name of Patentee or Applicant of Cited Document	Class	Subclass	Filing Date if Appropriate
	AN	2002/0102490	8/1/02	Ito et al.			
	AO	Serial No. 09/771,149		Ito et al.			1/26/01
	AP	Serial No. 09/771,261		Brock et al.			1/26/01
	AQ	Serial No. 09/794,466		Allen et al.			2/26/01

OTHER DOCUMENTS — NONPATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), Title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T
	AR	Abe et al. (1995), "Study of ArF Resist Material in Terms of Transparency and Dry Etch Resistance," <i>Journal of Photopolymer Science and Technology</i> 8(4):637-642.	
	AS	Allen et al. (1995), "Resolution and Etch Resistance of a Family of 193 nm Positive Resists," <i>Journal of Photopolymer Science and Technology</i> 8(4):623-636.	
	AT	Endert et al. (1999), "Microstructuring with 157 nm Laser Light," <i>Proceedings of SPIE-The International Society for Optical Engineering</i> 3618:413-417.	
	AU	Onishi et al. (1991), "Acid Catalyzed Resist for KrF Excimer Laser Lithography," <i>Journal of Photopolymer Science and Technology</i> 4(3):337-340.	

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Examiner Signature		Date Considered	
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.